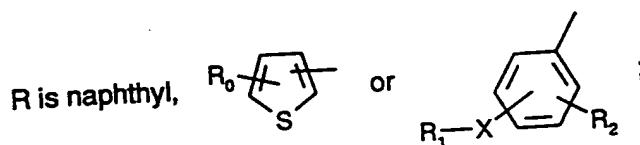
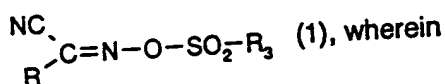


Abstract of the Disclosure

The invention describes the use of oxime alkyl sulfonate compounds of formula 1



R₀ is either an R₁-X group or R₂;

X is a direct bond, an oxygen atom or a sulfur atom;

R₁ is hydrogen, C₁-C₄alkyl or a phenyl group which is unsubstituted or substituted by a substituent selected from the group consisting of chloro, bromo, C₁-C₄alkyl and C₁-C₄alkyloxy;

R₂ is hydrogen or C₁-C₄alkyl; and

R₃ is straight-chain or branched C₁-C₁₂alkyl which is unsubstituted or substituted by one or more than one halogen atom;

as photosensitive acid generator in a chemically amplified photoresist which is developable in alkaline medium and which is sensitive to radiation at a wavelength of 340 to 390 nanometers and correspondingly composed positive and negative photoresists for the above-mentioned wavelength range.